WHAT IS CLAIMED IS:

1. A method for fabricating an organic thin film comprising the steps of:

forming an undercoating film made of silicon nitride or silicon nitride oxide on a substrate;

wet-cleaning said undercoating film using a cleaning liquid;

irradiating far ultraviolet ray onto said undercoating film of which wet-cleaning has been completed; and

forming an organic thin film with a thickness of about 100nm or thinner on said undercoating film onto which far ultraviolet ray has been irradiated by turning said substrate and supplying a liquid organic material onto said substrate.

2. The method for fabricating an organic thin film according to claim 1, wherein said step of wet-cleaning includes the step of applying ultrasonic wave in said cleaning liquid.

3. The method for fabricating an organic thin film according to claim 1, further comprising a step of forming another organic thin film on said undercoating film and then removing this organic thin film between the step of depositing said undercoating film and the step of wet-cleaning.

4. The method for fabricating an organic thin film according to claim 1, wherein said step of irradiating far ultraviolet ray includes a step of performing heat

treatment on said substrate.

5. The method for fabricating an organic thin film according to claim 1, wherein a total amount of said liquid organic material used in the step of forming said organic thin film is at least 0.8ml.

6. A method for fabricating an organic thin film comprising the steps of:

forming an undercoating film made of silicon nitride or silicon nitride oxide on a substrate;

wet-cleaning said undercoating film using a cleaning liquid; and

forming an organic thin film with a thickness of about 100nm or thinner on said undercoating film of which wet-cleaning has been completed by turning said substrate and supplying a liquid organic material onto said substrate;

wherein said organic material contains at least one solvent selected from the group consisting of propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether, ethyl lactate, methyl methoxy propionate, ethyl ethoxy propionate, 2-heptanone, ethyl pyruvate, diethylene glycol monomethyl ether, methyl cellosolve acetate, propylene glycol monoethyl ether acetate, ethyl methoxy propionate, methyl lactate, methyl pyruvate and diethylene glycol dimethyl ether.

7. The method for fabricating an organic thin film according to claim 6, wherein said step of wet-cleaning

includes the step of applying ultrasonic wave in said cleaning liquid.

8. The method for fabricating an organic thin film according to claim 6, further comprising the step of forming another organic thin film on said undercoating film and then removing this organic thin film between the step of forming said undercoating film and the step of wet-cleaning.

9. The method for fabricating an organic thin film according to claim 6, wherein a total amount of said liquid organic material used in the step of forming said organic thin film is at least 0.8ml.

10. A method for fabricating an organic thin film comprising the steps of:

forming an undercoating film made of silicon nitride or silicon nitride oxide on a substrate;

irradiating far ultraviolet ray onto said undercoating film; and

forming an organic thin film with a thickness of about 100nm or thinner on said undercoating film onto which far ultraviolet ray has been irradiated, by turning said substrate and supplying a liquid organic material onto said substrate;

wherein said organic material contains at least one solvent selected from the group consisting of propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether, ethyl lactate, methyl methoxy

propionate, ethyl ethoxy propionate, 2-heptanone, ethyl pyruvate, diethylene glycol monomethyl ether, methyl cellosolve acetate, propylene glycol monoethyl ether acetate, ethyl methoxy propionate, methyl lactate, methyl pyruvate and diethylene glycol dimethyl ether.

11. The method for fabricating an organic thin film according to claim 10, wherein said step of irradiating far ultraviolet ray includes a step of heating said substrate.

12. The method for fabricating an organic thin film according to claim 10, wherein a total amount of said liquid organic material used in the step of forming said organic thin film is at least 0.8ml.